

## Electronic Patent Application Fee Transmittal

<b>Application Number:</b>	10578683			
<b>Filing Date:</b>	09-May-2006			
<b>Title of Invention:</b>	FABRICATION METHOD OF EXTREME ULTRAVIOLET RADIATION MASK MIRROR USING ATOMIC FORCE MICROSCOPE LITHOGRAPHY			
<b>First Named Inventor/Applicant Name:</b>	Hai Won Lee			
<b>Filer:</b>	Rebecca Mather McNeill/Jennifer Arguelles			
<b>Attorney Docket Number:</b>	05823.0283			
Filed as Small Entity				
<b>U.S. National Stage under 35 USC 371 Filing Fees</b>				
<b>Description</b>	<b>Fee Code</b>	<b>Quantity</b>	<b>Amount</b>	<b>Sub-Total in USD(\$)</b>
<b>Basic Filing:</b>				
<b>Pages:</b>				
<b>Claims:</b>				
<b>Miscellaneous-Filing:</b>				
<b>Petition:</b>				
<b>Patent-Appeals-and-Interference:</b>				
<b>Post-Allowance-and-Post-Issuance:</b>				
Utility Appl issue fee	2501	1	755	755
Publ. Fee- early, voluntary, or normal	1504	1	300	300

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Extension-of-Time:				
Miscellaneous:				
Total in USD (\$)				1055